

“Influence of the Ar/O₂ ratio on the growth and biaxial alignment of yttria stabilized zirconia layers during reactive unbalanced magnetron sputtering”. Mahieu S, Ghekiere P, de Winter G, Depla D, de Gryse R, Lebedev OI, Van Tendeloo G, Thin solid films : an international journal on the science and technology of thin and thick films **484**, 18 (2005).
<http://doi.org/10.1016/j.tsf.2005.01.021>